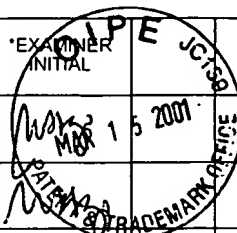


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FORM PTO,1449 (modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)		ATTY DOCKET NO. <div style="text-align: center; font-weight: bold;">35C.14179</div> APPLICATION NO. <div style="text-align: center; font-weight: bold;">09/722,454</div>	
		APPLICANT <div style="text-align: center; font-weight: bold;">YOUICHI ANDO, ET AL.</div>	
		FILING DATE <div style="text-align: center; font-weight: bold;">November 28, 2000</div>	GROUP <div style="text-align: center; font-weight: bold;">Unassigned</div>

U.S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	5066883	11/91	Yoshioka, et al.	313	309	
	5528108	6/96	Cisneros	315	169.3	
	5569974	10/96	Morikawa, et al.	313	310	
	5682085	10/97	Suzuki, et al.	315	169.1	

FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT
Wmz	EP	0660357	6/95	Europe	—	—	
Wmz	EP	1-31332	2/89	Japan	—	—	Abstract
Wmz	JP	2-257551	10/90	Japan	—	—	Abstract
Wmz	JP	3-55738	3/91	Japan	—	—	Abstract and USP 5,569,974
Wmz	JP	4-28137	1/92	Japan	—	—	Abstract and USP 5,692,085
Wmz	JP	7-235255	9/95	Japan	—	—	Abstract and EPA 660357
Wmz	JP	8-106847	6/97	Japan	—	—	Abstract and USP 5,528,108

OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)	
Wmz	• Meyer, et al.; "Recent Development on 'Microtips' Display At Leti"; Tech. Dig. of IVMC 91, Nagahama 1991, pp. 6-9.
Wmz	• Hartwell, et al.; "Strong Electron Emission From Patterned Tin-Indium Oxide Thin Films"; Tech. Dig. 1 EDM, Tech. Pig., Dec. 1-3, 1975, Wash. D.C., pp. 519-521 (1976).
Wmz	• Spindt, et al.; "Physical Properties Of Thin-Film Field Emission Cathodes With Molybdenum Cones"; J. Appl. Phys. Vol. 47, No. 12, Dec. 1976, pp. 5248-5263.
Wmz	• C.A. Mead; "Operation Of Tunnel-Emission Devices"; J. Appl. Phys. Vol. 32, No. 4, April 1961, pp. 646-652.
Wmz	• Elinson, et al.; "The Emission Of Hot Electrons And The Field Emission Of Electrons From Tin Oxide"; Radio Engineering and Electronic Physics, Vol. 10, pp. 1290-1296, (1965).

EXAMINER <i>maurice p. murray</i>	DATE CONSIDERED <i>9/23/03</i>
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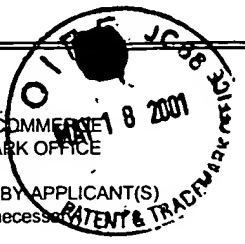
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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FORM PTO-1449 (modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF REFERENCES CITED BY APPLICANT(S) (Use several sheets if necessary)		<table border="1" style="width:100%; border-collapse: collapse;"><tr><td style="width:50%;">ATTY DOCKET NO. 35C.14179</td><td style="width:50%;">APPLICATION NO. 09/722,454</td></tr><tr><td colspan="2">APPLICANT YOUICHI ANDO, ET AL.</td></tr><tr><td>FILING DATE November 28, 2000</td><td>GROUP Unassigned</td></tr></table>		ATTY DOCKET NO. 35C.14179	APPLICATION NO. 09/722,454	APPLICANT YOUICHI ANDO, ET AL.		FILING DATE November 28, 2000	GROUP Unassigned
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FOREIGN PATENT DOCUMENTS									
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT		
OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)									
<i>msj</i>	o	G. Dittmer, "Electrical Conduction And Electron Emission Of Discontinuous Thin Films"; Thin Solid Films, Vol. 9, pp. 317-328 (1972).							
<i>msj</i>	i	Dyke, et al., "Field Emission", Advances in Electronics and Electron Physics, Vol. III, Academic Press, 89-184 (1956).							
<i>msj</i>	d	Araki, et al., "Electroforming and Electron Emission of Carbon Thin Films"; J. Vac. Soc. Japan, Vol. 26, No. 1, pp. 22-29 (1981).							
EXAMINER <i>Marialy pml:ag</i>				DATE CONSIDERED <i>9/23/03</i>					

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	APPLICANT YOUICHI ANDO, ET AL.	
	FILING DATE November 28, 2000	GROUP 2879

U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT

OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)		
<i>msky</i>		High Voltage Technology", Electric Institute, Ohm Company, pages 38, 39 (1981).
EXAMINER	<i>Manichu Pontiago</i>	DATE CONSIDERED 9/23/03

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.